

Notice of Allowability

Application No.

10/612,554

Applicant(s)

YANG ET AL.

Examiner

Art Unit

David L. Hogans

2813

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address--

All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance (PTOL-85) or other appropriate communication will be mailed in due course. **THIS NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHTS.** This application is subject to withdrawal from issue at the initiative of the Office or upon petition by the applicant. See 37 CFR 1.313 and MPEP 1308.

1. ☒ This communication is responsive to the Remarks filed on September 28, 2004.
2. ☒ The allowed claim(s) is/are 1-10.
3. ☒ The drawings filed on 01 July 2003 are accepted by the Examiner.
4. ☐ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
 - a) ☐ All b) ☐ Some* c) ☐ None of the:
 1. ☐ Certified copies of the priority documents have been received.
 2. ☐ Certified copies of the priority documents have been received in Application No. _____.
 3. ☐ Copies of the certified copies of the priority documents have been received in this national stage application from the International Bureau (PCT Rule 17.2(a)).

* Certified copies not received: _____.

Applicant has THREE MONTHS FROM THE "MAILING DATE" of this communication to file a reply complying with the requirements noted below. Failure to timely comply will result in ABANDONMENT of this application.

THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.

5. ☐ A SUBSTITUTE OATH OR DECLARATION must be submitted. Note the attached EXAMINER'S AMENDMENT or NOTICE OF INFORMAL PATENT APPLICATION (PTO-152) which gives reason(s) why the oath or declaration is deficient.
 6. ☐ CORRECTED DRAWINGS (as "replacement sheets") must be submitted.
 - (a) ☐ including changes required by the Notice of Draftsperson's Patent Drawing Review (PTO-948) attached
 - 1) ☐ hereto or 2) ☐ to Paper No./Mail Date _____.
 - (b) ☐ including changes required by the attached Examiner's Amendment / Comment or in the Office action of Paper No./Mail Date _____.
- Identifying indicia such as the application number (see 37 CFR 1.84(c)) should be written on the drawings in the front (not the back) of each sheet. Replacement sheet(s) should be labeled as such in the header according to 37 CFR 1.121(d).
7. ☐ DEPOSIT OF and/or INFORMATION about the deposit of BIOLOGICAL MATERIAL must be submitted. Note the attached Examiner's comment regarding REQUIREMENT FOR THE DEPOSIT OF BIOLOGICAL MATERIAL.

Attachment(s)

1. ☒ Notice of References Cited (PTO-892)
2. ☐ Notice of Draftsperson's Patent Drawing Review (PTO-948)
3. ☐ Information Disclosure Statements (PTO-1449 or PTO/SB/08),
Paper No./Mail Date _____
4. ☐ Examiner's Comment Regarding Requirement for Deposit
of Biological Material
5. ☐ Notice of Informal Patent Application (PTO-152)
6. ☐ Interview Summary (PTO-413),
Paper No./Mail Date _____
7. ☐ Examiner's Amendment/Comment
8. ☒ Examiner's Statement of Reasons for Allowance
9. ☐ Other



CARL WHITEHEAD, JR.
SUPERVISORY PATENT EXAMINER
TECHNOLOGY CENTER 2800

DETAILED ACTION

This Office Action is in response to the Remarks filed on September 28, 2004.

Election/Restrictions

The restriction requirement of June 28, 2004, had been withdrawn. The Applicant's contention that "the Examiner has searched and cited art related ... which can be used with reference to Claims 6-10 as well" is deemed meritorious. Accordingly the restriction requirement is withdrawn.

Allowable Subject Matter

1. Claims 1-10 are allowed.
2. The following is an examiner's statement of reasons for allowance.

The prior art of record fails to teach or suggest, in combination with the other claimed features, forming a first tapered contact opening, using the photoresist contact opening, into the dielectric layer, forming the first tapered contact opening with a bottom opening smaller than the photoresist contact opening; forming a second tapered contact opening, using the first tapered contact opening, into the dielectric liner layer, forming the second tapered contact opening with a bottom opening open to the active region for a smaller region than the active region with which the dielectric liner layer is in contact; removing the photoresist; and forming a conductive material in the first and second tapered contact openings to form a contact in contact with the active region, the dielectric liner layer, and the dielectric layer.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably

accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Conclusion

3. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure.

6,060,385 to Givens teaches an interconnect structure but fails to teach wherein the first opening is a tapered contact opening in contact with an active region through the second tapered contact opening.

5,399,532 to Lee et al. teaches an interconnect structure with first and second tapered openings but fails to explicitly teach wherein the first tapered contact opening possesses a bottom opening smaller than the photoresist contact opening.

5,750,441 to Figura et al. teaches a pair of multi-layered structures with a first tapered contact opening but fails to teach sidewall spacers and a second tapered contact opening.

6,731,008 to Tomita et al. teaches an interconnect structure with a tapered opening but fails to explicitly teach a tapered opening formed within the dielectric liner layer.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to David L. Hogans whose telephone number is (571) 272-1691. The examiner can normally be reached on M-F (7:30-4:30).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Carl Whitehead Jr. can be reached on (571) 272-1702. The fax phone

Art Unit: 2813

number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

DH

